



1. Title:	Present status of laser-produced plasma EUV light source
2. Full names of all authors:	Akira Endo, Hideo Hoshino, Tatsuya Ariga, Taisuke Miura, Yoshifumi Ueno, Masaki Nakano, Hiroshi Komori, Georg Soumagne, Hakaru Mizoguchi, Akira Sumitani and Koichi Toyoda

3. Abstract body:

The development status of the key technologies for a HVM Laser Produced Plasma EUV light source will be presented. This includes the high-power RF-excited CO₂ laser, the Sn droplet target and the collector mirror lifetime enhancement (debris, ion mitigation). Basic experiments that support the development, e.g. a conversion efficiency of 2.8% has been obtained with a 15ns TEA CO₂ laser and a Sn wire, as well as a general outline of the system development, i.e. system scaling towards 50/115 and 180 W, will be given.

This work was supported by the New Energy and Industrial Technology Development Organization (NEDO), Japan.